

WET SCRUBBING INTENSIFICATION APPLIED TO HYDROGEN SULPHIDE REMOVAL IN WASTE WATER TREATMENT PLANT

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| 2 | SULPHIDE REMOVAL IN WASTE WATER TREATMENT PLANT |
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16 Abstract

17 Hydrogen sulphide removal in a Waste Water Treatment Plant at semi-industrial scale 18 in a compact wet scrubber has been investigated. The gas residence time in the scrubber was 19 reduced to 30 ms using a NaOCl caustic scrubbing solution. The contactor is composed of a 20 wire mesh packing structure where liquid and gas flow co-currently at high velocity (> 12 m.s⁻¹). H₂S removal percentages higher than 95% could be achieved whereas a moderate 21 22 pressure drop was measured (< 4000 Pa). Both the hydrodynamic and chemical conditions can influence the efficiency of the process. Correlations were developed to predict both the 23 24 pressure drop and the H₂S removal efficiency at given operating conditions.

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26

Résumé

27 Le traitement du sulfure d'hydrogène dans un laveur de gaz compact a été étudié à 28 l'échelle semi-industrielle en station d'épuration. Le temps de contact dans le laveur est réduit 29 à une trentaine de ms en utilisant une solution d'hypochlorite de sodium à pH basique. Le 30 contacteur se compose d'une structure tissée métallique dans laquelle le gaz et le liquide circulent à co-courant et grande vitesse (> 12 m.s⁻¹). Un abattement de l'H₂S de plus de 95% 31 32 peut être obtenu avec une perte de charge modérée (< 4000 Pa). A la fois les conditions 33 chimiques et hydrodynamiques influencent les performances de traitement. Des corrélations 34 ont été développées pour prédire la perte de charge mais aussi l'abattement dans des 35 conditions opératoires données.

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Keywords: Absorption, chemical scrubbing, compact scrubber, hydrogen sulphide,

- 38 odour control.
- 39

40 **INTRODUCTION**

41

42 Hydrogen sulphide is the major compound involved in odour emissions from WWTPs 43 (Gostelow, 2001). The strategy applied in WWTPs to reduce odour emissions consists to 44 ventilate the odorous stages (pre-treatment, biological aeration, sludge treatment, etc) and to 45 bring the collected air into a single odour control unit in which different processes can be 46 implemented (Busca and Chiara, 2003). The most common process used is the packed towers, 47 in which pollutants are removed by chemical scrubbing (Bonnin, 1991; Chen et al., 2001). 48 Chemical scrubbing involves pollutant mass transfer in an aqueous phase and subsequent 49 reactions with acidic, basic or oxidant reagent(s). Most of the time, H₂S is oxidised by sodium hypochlorite (NaClO) in an alkaline solution ($pH \ge 9$): 50

51

52
$$H_2S + 4 \operatorname{NaOCl} + 2 \operatorname{NaOH} \rightarrow \operatorname{Na}_2SO_4 + 4 \operatorname{NaCl} + 2 H_2O$$
 (1)

53

 H_2S consumption in the liquid phase allows to maintain a driving force in order to achieve mass transfer. Moreover, when the reaction kinetics is fast compared to the mass transfer kinetics, mass transfer enhancement is involved.

57 Chemical scrubbing in packed towers has revealed high investment and operating 58 costs (Couvert et al., 2008). Indeed, it implies the construction of high and large wet 59 scrubbers. Moreover, long and expensive pipes and powerful fans are necessary to bring the waste air to the odour control unit. An alternative leading to the reduction of investment and 60 61 operating costs could consist in treating odorous gas near each emission source in compact 62 scrubbers in which the fluid residence time is significantly shorter. Process intensification, 63 through mass transfer and superficial velocity enhancement inside the contactor, allows to decrease the reactor size and the fluid residence time. 64

The key element of the new Aquilair PlusTM process is a patented high voidage 65 contactor specially adapted to compact wet scrubbing (Sanchez et al., 2007a ; Biard et al., 66 2009a). This down flow co-current contactor consists of a wire mesh packing structure where 67 gas flows at high velocity ($U_{SG} > 12 \text{ m.s}^{-1}$). The liquid, swept along by the gas, collides with 68 69 the wire mesh and is dispersed into fine droplets. At the laboratory scale, high mass transfer 70 rate has been demonstrated for a moderate pressure drop (Sanchez et al., 2007b). The gas 71 residence time could be reduced to less than 50 ms instead of about 1 or 2 seconds in packed 72 towers to treat H₂S (Sanchez et al., 2007c). At the laboratory scale, an increase of the 73 superficial gas velocity (U_{SG}) and in a minor extent of the superficial liquid velocity (U_{SL}) led to better interfacial area (a^0) and gas and liquid mass transfer coefficients ($k_G a^0$ and $k_I a^0$) due 74 75 to a higher energy loss (Sanchez et al., 2007b; Biard et al., 2009b).

The aim of this study was to test the potentialities of the process at the semi-industrial 76 scale (designed to treat gas flow rates Q_G ranging between 1500 and 2000 m³.h⁻¹) with a real 77 78 gaseous effluent extracted from a WWTP. Scale-up difficulty is due to wall effects reduction 79 at larger contactor sizes, which can induce both lower liquid dispersion and mass transfer rate. 80 Between the laboratory and the semi-industrial scales, the spatial disposition of the wire 81 meshes was modified to provide higher tortuosity. Both the pressure drop (ΔP) and the H₂S 82 removal percentage were determined versus several parameters. The influence of the 83 superficial gas velocity (U_{SG}) , the superficial liquid velocity (U_{SI}) , the pH, the sodium hypochlorite concentration of the scrubbing liquid ([ClO⁻]) and the H₂S inlet concentration 84 85 ([H₂S]_{Gi}) was characterised. A model was developed in order to predict H₂S removal 86 efficiency and pressure drop in the scrubber.

87

89 MATERIALS AND METHODS

90

91 The contactor is composed of a wire mesh structure of 200 mm diameter (void fraction 92 \approx 99.0%). The initial height (H_r) of the packing was 600 mm but after the first experiments, 93 the packing was compressed to 500 mm. The polluted air was pumped from the extraction 94 pipe of the WWTP with a fan (AEIB) (Figure 1). By opening a valve placed before the fan, it 95 was possible to dilute polluted air with clean air to modify the inlet H₂S concentration ([H₂S]_{G,i} in ppmv: Part Per Million by Volume). The gas flow rate Q_G was measured and 96 97 controlled by means of a Pitot Tube (Deltabar S PMD 70 from Endress Hauser) and a 98 frequency variator (Allen Bradley). The liquid injection upstream the contactor was insured 99 by a spray nozzle SpiralJet (Spraying System). A 400 L tank allowing to store the scrubbing 100 liquid and to separate the gas-liquid mixture was placed downstream the contactor. A droplet 101 separator was placed downstream the tank before emission in atmosphere (Horus 102 Environmement). The storage tank was filled with ground water previously softened. Reagents 103 (NaOCl and NaOH provided by Brenntag) were pumped from 1000 L tanks to the storage 104 tank by two metering pumps Gamma L (Prominent). The scrubbing liquid was recirculated to 105 the top of the contactor by a centrifugal pump (MDFL from Iwaki) and the liquid flow rate 106 was controlled by an electromagnetic flowmeter (Promag 10 P from Endress Hauser).

107 A bypass located after the recirculation pump allowed the measurement of the pH, 108 Redox, temperature and conductivity of the scrubbing liquid by specific probes (Endress 109 Hauser). The pH and the hypochlorite concentration of the scrubbing liquid, clean water 110 supply and drain were regulated respectively by the pH, the Redox and the conductivity 111 measurements. Pressure measurements upstream and downstream the contactor involved two 112 pressure sensors Cerabar S PMC 71 (Endress Hauser). The H₂S concentration was 113 continuously measured upstream ($[H_2S]_{G,i}$) and downstream ($[H_2S]_{G,o}$) the contactor by 114 means of two electrochemical sensors Polytron (Dräger). The H₂S removal efficiency was
115 defined as:

116

117 Eff =
$$\frac{[H_2S]_{G,i} - [H_2S]_{G,o}}{[H_2S]_{G,i}} = 1 - \frac{[H_2S]_{G,o}}{[H_2S]_{G,i}}$$
 (2)

118

119 **Results and discussion**

120

Influence of the hydrodynamic conditions on the pressure drop and the H₂S removal 122

123 Through the transparent PVC pipe contactor, a strong dispersion of the liquid into small droplets was observed for U_{SG} higher than 13-14 m.s⁻¹. The ratio L/G, which represents 124 125 the ratio of the recirculated liquid mass flow rate and the treated gas mass flow rate, is 126 generally close to 3 when H₂S is treated in packed columns (Bonnin, 1991). The pressure drop ΔP was measured for $600 < Q_G < 2800~m^3.h^{-1}$ and $3500 < Q_L < 8000~L.h^{-1}$ (L/G from 1.1 127 to 11.2). It could be observed that ΔP strongly increased with U_{SG}, since the gas is the 128 129 continuous phase, and with a minor extent with U_{SL} (Figure 2). This energy loss is partly 130 transferred to the liquid to achieve a better liquid dispersion and mixing. As a consequence, 131 when U_{SG} increases, mass transfer rate increases, leading to an improvement of the H₂S 132 removal efficiency (Figure 3). Hence, a compromise must be realised for the selection of U_{SG} 133 in order to limit the pressure drop to ensure the process economic viability. The pressure drop 134 per reactor height unit $(\Delta P/H_r)$ could be well correlated to the gas and liquid superficial 135 velocities U_{SG} and U_{SL}:

137
$$\frac{\Delta P}{H_{r}}(Pa.m^{-1}) = 285.7 \times U_{SG}^{1.68} \times U_{SL}^{0.47} = 11.9 \times U_{SG}^{2.15} \times \left(\frac{L}{G}\right)^{0.47}$$
(3)

139 The determination coefficient (R^2) between the experimental and the predicted 140 pressure drops is 99.94 %. However, this equation is valid only for this packing geometry and 141 diameter and should not be used for scale-up.

142 Otherwise, Figure 4 demonstrates that an increase of U_{SL} (proportional to L/G) at a given gas flow rate induces a significant better H₂S removal. This evolution could be 143 attributed to a better hydrodynamic behaviour. Indeed, Sanchez et al. (2007a) demonstrated at 144 the laboratory scale that $k_L a^0$ increases with the liquid velocity (or flow rate). Moreover, L/G 145 146 increasing implies that more liquid flows in the contactor (the liquid hold-up increases), 147 which allows to limit the pH and hypochlorite concentration decrease due to the oxidation 148 reaction. However, increasing the liquid flow rate generates a higher pressure drop and 149 consumes more electrical power for the recirculation, which leads to a more expensive 150 operation.

151

152 Influence of the chemical conditions on the H₂S removal

153

154 Chemical conditions can notably influence the H₂S removal. Now, no significant variation of the H₂S removal was observed when the pH varied between 9.5 and 11 (not 155 156 presented here). However, for a pH close to 9.5, the formation of a yellow precipitate of 157 colloidal sulphur was observed whereas for a pH close to 11, the formation of a white 158 precipitate of carbonates could be noticed (due to the reaction between NaOH and CO₂ 159 present in atmospheric air). Then, all the results presented in this paper were performed with a 160 pH ranging between 10 and 10.5 (low and high pH thresholds of the regulation). Figure 4 161 demonstrates a positive influence of the sodium hypochlorite concentration on the H₂S

162 removal. When the hypochlorite concentration increases, the oxidation kinetics improvement 163 favours H₂S oxidation in the liquid film which enhances the removal efficiency. This result is 164 particularly interesting considering that it is a low cost operating solution comparing to an increasing of U_{SG} and U_{SL} . Several experiments were carried out for $U_{SG} = 14.1 \text{ m.s}^{-1}$, $U_{SL} =$ 165 0.093 m.s^{-1} , 10 < pH < 10.5 and $[ClO^{-}] \approx 3 \text{ g.L}^{-1}$, but with $[H_2S]_{G,i}$ varying from 6 to 80 ppmv. 166 167 The H₂S removal was not significantly different and close to 96 %. The H₂S removal is consequently independent of the inlet concentration. However, one has to keep in mind that 168 169 working with high inlet concentration favours hydroxide anion and hypochlorite 170 consumptions in the scrubber. Consequently, the amount of H₂S treated must be lower than 171 twice the amount of hydroxide anion and 4 times the amount of hypochlorite in the scrubbing 172 liquid at the inlet. With a classical H₂S inlet concentration in WWTP of 5-6 ppmv, it is 173 therefore possible to reach an H₂S outlet concentration ranging between 0.1 and 0.2 ppmv, 174 which is close to the values that deodorisation unit designers guaranty (Verguet et al., 2008).

175

176 H₂S removal modelling

177

Assuming a plug flow of the gas phase, in an elementary contactor height (dz in m),
the H₂S transferred flow (dN in mol.s⁻¹) can be expressed as:

180

181
$$dN = k_{L}a^{0}E([H_{2}S]_{L}^{*} - [H_{2}S]_{L})S_{col}dz = K_{L}a^{0}\left(\frac{[H_{2}S]_{G}}{H_{H_{2}S}} - [H_{2}S]_{L}\right)S_{col}dz$$
(4)

182

183 k_L and K_L are respectively the local and overall liquid mass transfer coefficients (m.s⁻¹), a⁰ is the volumetric interfacial area (m².m⁻³), S_{col} the contactor section (m²), $[H_2S]_L^*$ the 185 H_2S concentration in the liquid phase at the gas-liquid interface (mol.m⁻³) and $[H_2S]_L$ the H_2S concentration in the bulk of the liquid (mol.m⁻³). H'_{H_2S} is the Henry's law constant in water of H₂S at 293 K (= 0,363 mol L⁻¹ / mol L⁻¹). E is the enhancement factor, equal to the rate of H₂S transferred when the reaction occurs divided by the rate of H₂S transferred when no reaction occurs (E \ge 1). K_L is linked to k_L and k_G (the local liquid and gas mass transfer coefficients) and E by:

191

192
$$\frac{1}{K_{L}} = \frac{1}{Ek_{L}} + \frac{1}{H_{H_{2}S}^{'}k_{G}}$$
 (5)

193

Oxidation of H₂S by hypochlorite at basic pH is fast and happens in the liquid film at 194 195 the vicinity of the gas-liquid interface (Danckwerts, 1970). It means that H₂S is completely consumed in the liquid film by the oxidation reaction, leading to E >> 1 and $[H_2S]_L \approx 0$. In 196 197 this case, the first ratio of the right-hand terms of the Equation (5) may become negligible (instantaneous surface reaction) showing that all the resistance for mass transfer can be 198 199 located in the gas film. However, the results demonstrated that the removal efficiency 200 increased with the hypochlorite concentration, i.e. with the reaction kinetics, which clearly 201 shows that a part of the resistance for mass transfer is still located in the liquid film and can 202 not be neglected. Consequently, E must be estimated and depends on two dimensionless numbers: the Hatta number for a 2nd order kinetics (Ha) and the enhancement factor for an 203 204 infinitely fast reaction (E_i) (Danckwerts, 1970):

205

206
$$E = Ha = \frac{\sqrt{D_{H_2S,w}[ClO^-]k_{ox}}}{k_L}$$
 and $E_i = \frac{D_{ClO^-,w}[ClO^-]}{D_{H_2S,w}[H_2S]_L^*}$ (6)

 $k_{ox} \text{ is the apparent kinetics constant (L.mol⁻¹.s⁻¹) of the oxidation reaction and D_{H_2S,w}$ $and D_{ClO⁻,w} are respectively the diffusion coefficients of H_2S (1.6 10⁻⁶ m².s⁻¹) and ClO⁻ (1.3$ 10⁻⁶ m².s⁻¹) in water. The Hatta number represents the maximum pollutant conversion in theliquid film compared with its maximum transport through the film.

According to usual hypochlorite concentrations in the scrubbing liquid (> 0.1 g.L^{-1}), hypochlorite is in great excess comparing to hydrogen sulphide at the gas-liquid interface. In this case, the kinetics is pseudo-first order and the enhancement factor E is equal to Ha considering that this last number is large (see Table 1) but significantly lower E_i (which is in the range 4 000-92 000 at the scrubber inlet, depending on [ClO⁻] and [H₂S]_{G,i}).

The amount of hydrogen sulphide treated in the scrubber is negligible comparing to the amount of hypochlorite at the inlet. The hypochlorite concentration, and by the way the Hatta number, are consequently constant in the scrubber, assuming that k_{ox} does not depend in a great extent of the pH which should decrease due to the hydroxide anion consumption. Therefore:

222

223
$$\frac{1}{K_{L}} = \frac{1}{k_{L}} \frac{1}{\sqrt{D_{H_{2}S, w}[ClO^{-}]k_{ox}}}}{k_{L}} + \frac{1}{H_{H_{2}S}^{'}k_{G}} = \frac{1}{\sqrt{D_{H_{2}S, w}[ClO^{-}]k_{ox}}}} + \frac{1}{H_{H_{2}S}^{'}k_{G}}$$
(7)

224

According to the Equation (7), the Equation (4) can be rewritten:

226

227
$$dN = \frac{a^{0}}{\frac{1}{\sqrt{D_{H_{2}S,w}[ClO^{-}]k_{ox}}} + \frac{1}{H_{H_{2}S}k_{G}}} \frac{[H_{2}S]_{G}}{H_{H_{2}S}} S_{col}dz$$
(8)

229 By integration considering the height of the scrubber (H_r) , an analytical equation of the 230 overall flow of H₂S transferred is deduced:

231
$$N = \frac{a^{0}}{\frac{H_{H_{2}S}}{\sqrt{D_{H_{2}S,w}[ClO^{-}]k_{ox}}} + \frac{1}{k_{G}}} \frac{[H_{2}S]_{G,i} - [H_{2}S]_{G,o}}{ln([H_{2}S]_{G,i}/[H_{2}S]_{G,o})} S_{col}H_{r}$$
(9)

232

The gas phase mass balance between the inlet and the outlet leads after rearrangement to the equation (10):

235 Eff =
$$1 - \frac{[H_2S]_{G,o}}{[H_2S]_{G,i}} = 1 - \exp\left(-\frac{a^0}{\frac{H'_{H_2S}}{\sqrt{D_{H_2S,w}}[ClO^-]k_{ox}}} + \frac{1}{k_G}\frac{H_r}{U_{SG}}\right)$$
 (10)

236

237 This equation shows that the removal efficiency depends on the liquid dispersed state (through a^0), the turbulences in the gas phase (through k_G) and the oxidation kinetics (through 238 239 the product of $[ClO^{-}]$ and k_{ox}). Moreover, the efficiency is not influenced by the absorption 240 rate and the inlet H₂S concentration while hypochlorite and hydroxide anions are in excess. At 241 the laboratory scale (Sanchez et al., 2007b), and considering that the surface tension, density and viscosity of the scrubbing liquid are constant in the scrubber, hydrodynamic study 242 demonstrated that a^0 is a power law function of the superficial velocities: $a^0 = A \cdot U_{SG}^{\alpha} \cdot U_{SL}^{\beta}$ 243 244 with A, α and β three constants. Then, the Equation (10) can be rewritten:

245
$$Eff = 1 - \exp\left(-\frac{A \cdot U_{SG}^{\alpha - 1} \cdot U_{SL}^{\beta}}{\frac{H'_{H_2S}}{\sqrt{D_{H_2S,eau}}[ClO^-]k_{ox}}} + \frac{1}{k_G}H_r\right)$$
(11)

247 k_G should be influenced by U_{SG} . However, this variation can be neglected assuming 248 that U_{SG} has been slightly modified (from 14.1 to 18.6 m.s⁻¹). Therefore, k_G can be considered 249 as a constant. In the equation (11), A, α , β , k_G and k_{ox} are unknown. Due to the high H₂S 250 oxidation kinetics, k_{ox} should be in the range $10^6 - 5 \times 10^8$ L.mol⁻¹.s⁻¹. Consequently, A, α , β 251 and k_G have been determined (Table 1) for different values of k_{ox} in this range by numerical 252 fitting by the least square method trying to minimise the residual:

253

254 Residual =
$$\frac{1}{M} \sum_{i=1}^{M} \left(\frac{\text{Eff}_{exp} - \text{Eff}_{mod}}{\text{Eff}_{mod}} \right)^2$$
 with M = 18 the number of experimental data (12)

255

256 The model correlates with a good agreement the experimental results whatever the 257 value of kox selected with an average error lower than 1 % (Table 1). It demonstrates that assuming k_G as a constant is not aberrant. When the selected value of k_{ox} decreases, a^0 258 259 increases to compensate the lower enhancement by chemical reaction. At the laboratory scale, for similar superficial velocities, the average interfacial area and gas side mass transfer 260 coefficient were respectively in the range of 1500-2000 m².m⁻³ and 0.1-0.2 m.s⁻¹. These 261 values would be reached at the semi-industrial scale for a k_{ox} equal to 6×10^6 L.mol⁻¹ s⁻¹. 262 However, this value should be considered with care since the scale difference between the 263 laboratory and this study (and consequently the difference of Reynolds Number) may lead to 264 significant variations of the ranges of a^0 and k_{G} . 265

266

267 **Pressure drop and removal efficiency simulations**

268

Using Equations (3) and (11), simulations of the pressure drop and the removal efficiency for different operating conditions can be achieved. In order to limit the operating 271 cost of the process, a low value of U_{SG} (but sufficient to insure a strong liquid dispersion \Rightarrow $U_{SG} > 13 \text{ m.s}^{-1}$) must be selected. Consequently, two simulations have been realised at 13.3 272 and 14.1 m.s⁻¹ (respectively 1500 and 1600 m³.h⁻¹) using $k_{ox} = 6 \times 10^{6} \text{ L.mol}^{-1}.\text{s}^{-1}$ (Figure 5). 273 274 The choice of the quintet A, a, b, k_G and k_{ox} does not influence the results of the simulation. 275 Simulations confirm that the removal efficiency increases significantly with the hypochlorite concentration when lower than 3 $g.L^{-1}$. Moreover, the removal efficiency increases strongly 276 with the L/G ratio until 5. Using a hypochlorite concentration and a L/G ratio higher than 3 277 $g.L^{-1}$ and 5 is not necessary whatever the gas superficial velocity. Using such operating 278 279 conditions, the removal efficiency reaches 95 % for a moderate pressure drop which remains 280 lower than 3500-4000 Pa (maximal pressure drop to insure the process economic viability).

281

282 CONCLUSION

283

284 A new compact chemical scrubber was implemented in a WWTP. Results showed that 285 both hydrodynamic and chemical conditions significantly influence the H₂S removal. A 286 model was developed to predict the pressure drop and the H₂S removal at any given operating 287 condition. An interesting economic compromise was deduced for a moderate gas velocity and a high hypochlorite concentration. The new packing has not been optimised yet and some 288 289 improvement of the structure would certainly offer a lower pressure drop for a similar mass 290 transfer rate. To insure a high level of deodorisation, two scrubbers in series could be 291 implemented but the increasing of the pressure drop must be taken into account.

293 NOMENCLATURE

| 294 | [A] | concentration of the compound A |
|-----|-------------------------------|---|
| 295 | A, α and β | coefficients determined by numerical resolution |
| 296 | a^0 | interfacial area related to the volume of the contactor $(m^2.m^{-3})$ |
| 297 | $D_{H_2S,w} \\$ | diffusion coefficient of H_2S in water (m ² .s ⁻¹) |
| 298 | dz | infinitesimal height of contact (m) |
| 299 | E | enhancement factor |
| 300 | Ei | enhancement factor for an infinitely fast reaction |
| 301 | Eff | H_2S removal efficiency (%) |
| 302 | На | Hatta number |
| 303 | H_{H_2S} | H_2S Henry's constant in water |
| 304 | H _r | height of the contactor (m) |
| 305 | $k_{G}\left(K_{G} ight)$ | (overall) gas phase mass transfer coefficient $(m.s^{-1})$ |
| 306 | $k_L(K_L)$ | (overall) liquid phase mass transfer coefficient (m.s ⁻¹) |
| 307 | $k_G a^0 (K_G a^0)$ | (overall) gas phase volumetric mass transfer coefficient (s ⁻¹) |
| 308 | $k_{L}a^{0}$ ($K_{L}a^{0}$) | (overall) liquid phase volumetric mass transfer coefficient (s ⁻¹) |
| 309 | k _{ox} | kinetics constant of H_2S oxidation by hypochlorite at basic pH (L.mol ⁻¹ .s ⁻¹) |
| 310 | L/G | ratio of liquid and gas mass flow rates |
| 311 | N (dN) | (infinitesimal) flow of H_2S transferred (mol.s ⁻¹) |
| 312 | $Q_{G}\left(Q_{L} ight)$ | gas (liquid) volume flow rates (m ³ .h ⁻¹ or m ³ .s ⁻¹) |
| 313 | S_{col} | section of the contactor (m ²) |
| 314 | $U_{SG}\left(U_{SL}\right)$ | gas (liquid) superficial velocity (m.s ⁻¹) |
| 315 | WWTP | Waste Water Treatment Plant |
| 316 | | |
| 317 | | |

| 318 | Greek | letters |
|-----|-------|---------|
| | | |

319 ΔP pressure drop (Pa)

320 Indices

321 i inlet

- 322 G gas
- 323 L liquid
- 324 o outlet
- 325 * interface

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Figure captions

- 366 Figure 1. Set-up scheme.
- Figure 2. Pressure drop inside the scrubber versus U_{SG} for different U_{SL} ($Q_L = 3.5, 5.0, 6.5$ and $8.0 \text{ m}^3.\text{h}^{-1}$).
- 369 Figure 3. H_2S removal and pressure drop versus $U_{SG}\ (L/G$ = 3.5 ; 40 < $[H_2S]_{G,i}$ < 50 ppmv ;
- 370 [ClO⁻] \approx 1.5 g.L⁻¹; 10 < pH < 10.5).
- 371 Figure 4. H₂S removal and pressure drop versus L/G ($U_{SG} = 15 \text{ m.s}^{-1}$; 40 < [H₂S]_{G,i} < 50 ppmv 372 ; 10 < pH < 10.5).
- 373 Figure 5. Simulation of H₂S removal and pressure drop for two gas superficial velocities (U_{SG}
- $374 \qquad = 13.3 \text{ m.s}^{-1} \ (Q_G = 1500 \text{ m}^3.\text{h}^{-1}) \text{ and } 14.1 \text{ m.s}^{-1} \ (Q_G = 1600 \text{ m}^3.\text{h}^{-1})) \text{ for } 2 \leq L/G \leq 6 \text{ and } 1 \leq 100 \text{ m}^3.\text{h}^{-1} = 1000 \text{ m}^3.\text{h}^{-1}$
- 375 $[ClO^{-}] \le 4 \text{ g.L}^{-1}.$
- 376 377





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Figure 2



Figure 3







Table 1. Hatta range values (considering $k_L = 10^{-4} \text{ m.s}^{-1}$) and results of the numerical fitting for several values of k_{ox} .

| k_{ox} (L.mol ⁻¹ .s ⁻¹) | 1.0×10^{6} | 6.0×10^{6} | 1.0×10^{7} | 1.0×10^{8} | $5.0 	imes 10^8$ |
|--|---------------------|---------------------|---------------------|---------------------|------------------|
| Hatta range | 80-116 | 195-285 | 250-370 | 790-1 160 | 1 770-2 600 |
| A | 205.06 | 146.98 | 118.43 | 47.67 | 25.85 |
| α | 1.61 | 1.45 | 1.44 | 1.37 | 1.21 |
| β | 0.59 | 0.61 | 0.61 | 0.62 | 0.64 |
| $k_{G} (m.s^{-1})$ | 0.14 | 0.24 | 0.31 | 0.85 | 2.07 |
| a^0 average (m ² .m ⁻³) | 3 636 | 1 575 | 1 225 | 398 | 135 |
| $k_{G}a^0$ average (s ⁻¹) | 510 | 378 | 380 | 338 | 277 |
| $R^{2}(\%)$ | 97.44 | 97.97 | 97.99 | 98.06 | 97.94 |
| Average error (%) | 0.83 | 0.72 | 0.71 | 0.67 | 0.68 |